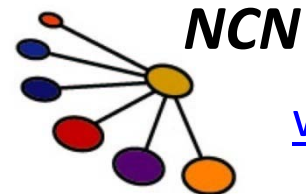


2009 NCN@Purdue-Intel Summer School  
Notes on Percolation and Reliability Theory

## Lecture 10

# Interface Damage and Negative Bias Temperature Instability

Muhammad A. Alam  
Electrical and Computer Engineering  
Purdue University  
West Lafayette, IN USA



**NCN**

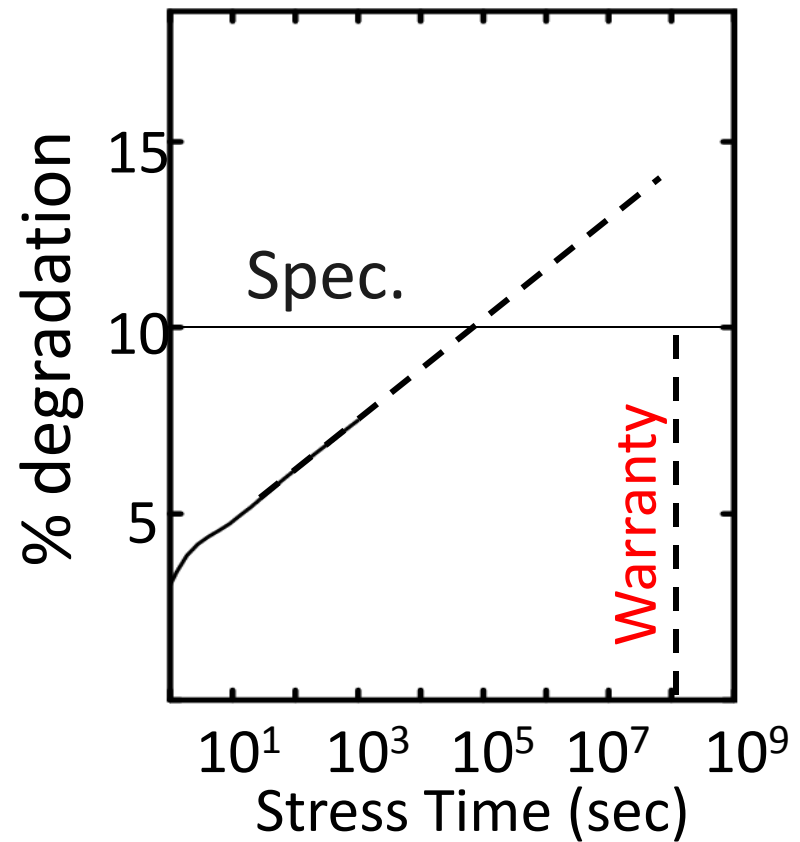
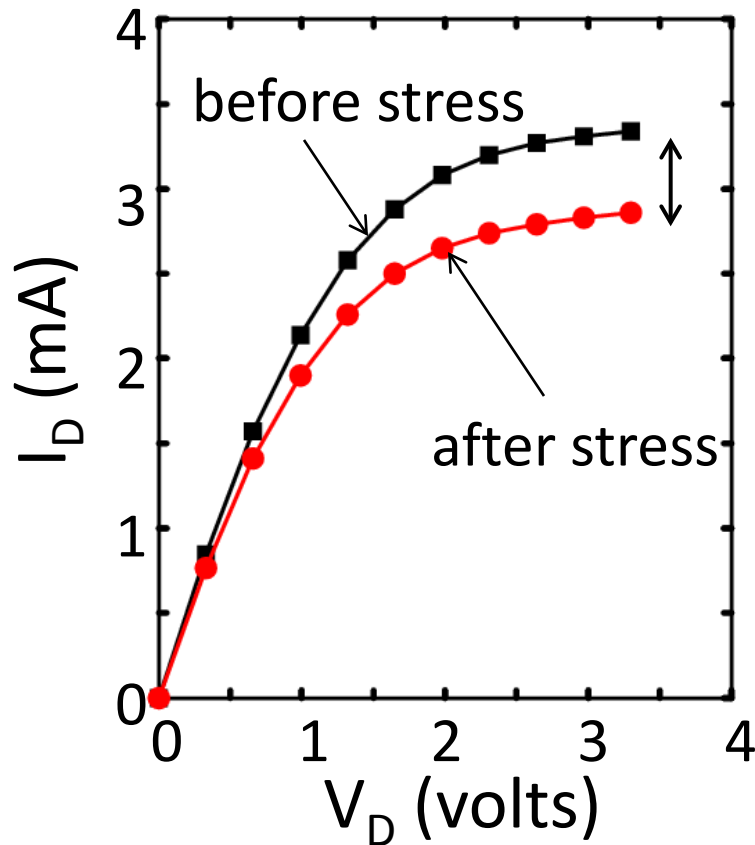
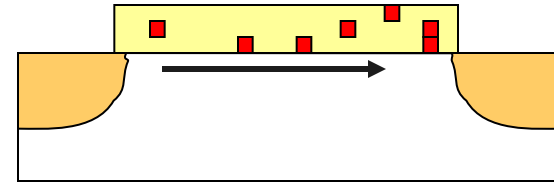
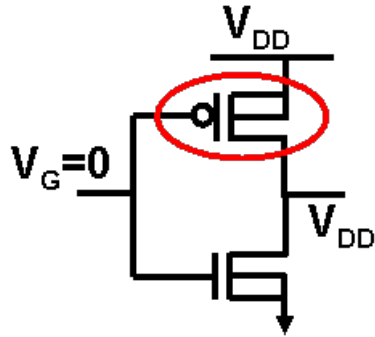
[www.nanohub.org](http://www.nanohub.org)

**PURDUE**  
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# Negative Bias Temperature Instability



# Characteristics of NBTI Degradation

$$I_D(t) \propto \mu \times [V_G - V_T(t)]$$

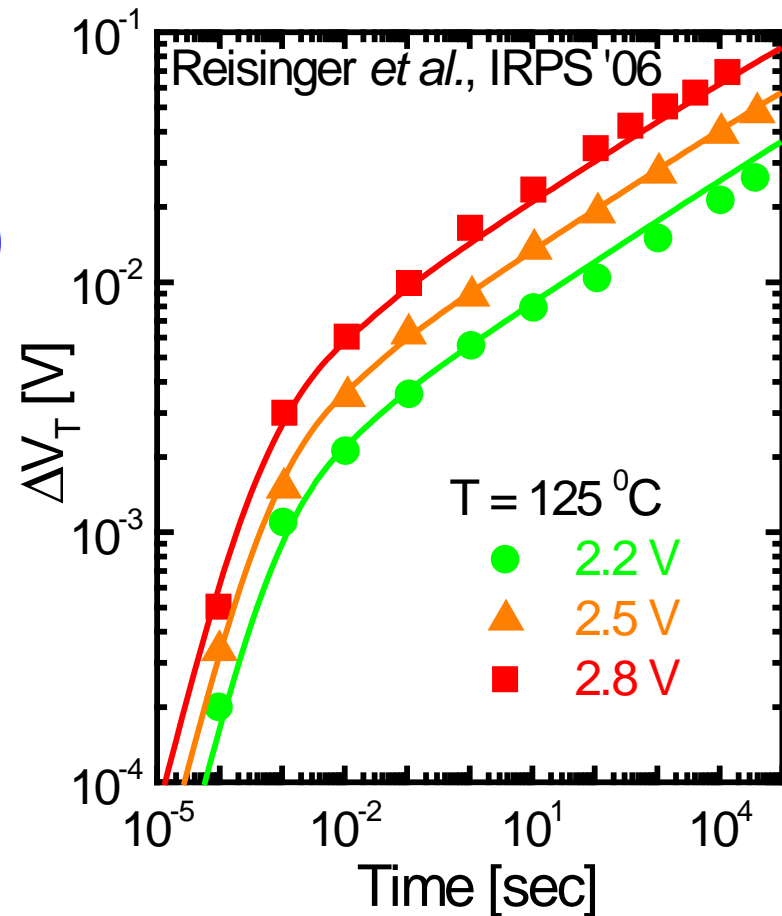
$$V_T(t) = V_T(t=0) + \Delta V_T(t)$$

$$\Delta V_T = A e^{-Ea/k_B T} t^n$$

○  $n \sim 0.16$

○  $Ea \sim 0.5 \text{ eV}$

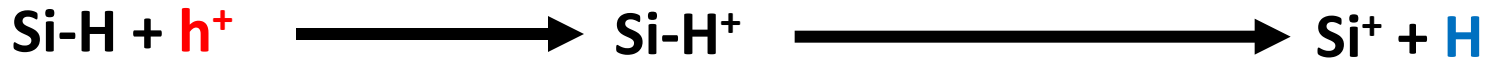
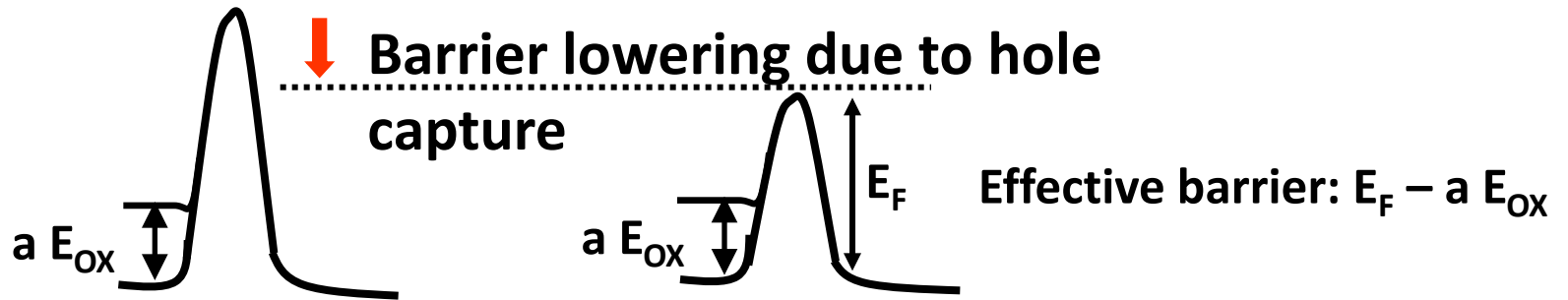
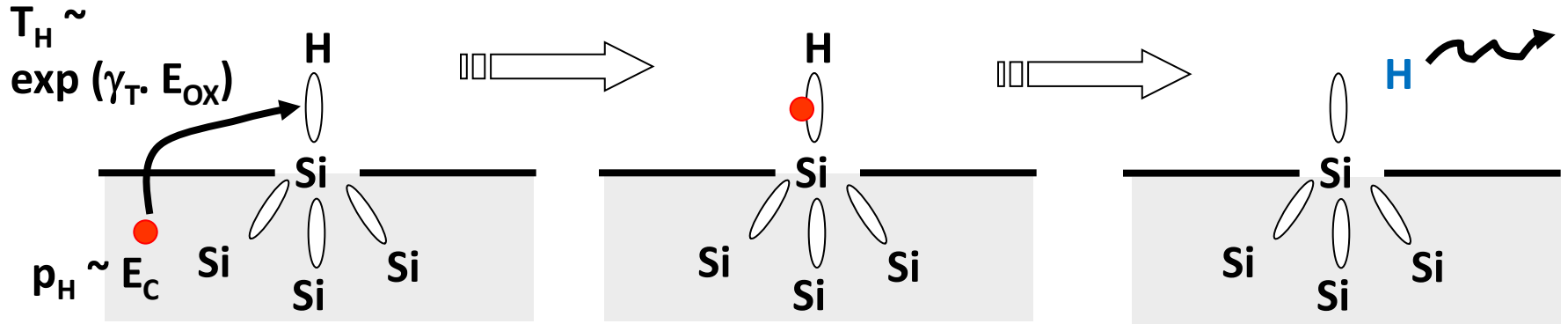
○  $A$  depends on  $E_{ox}$



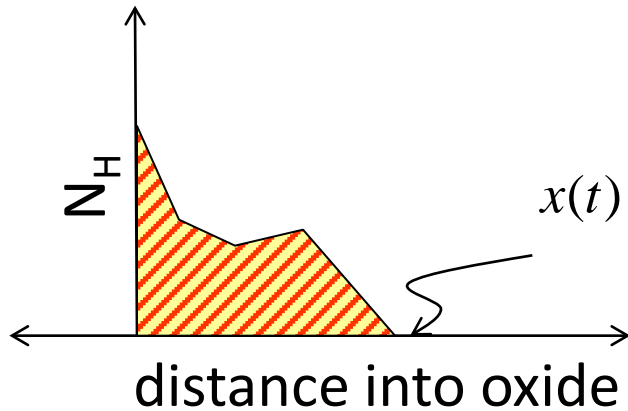
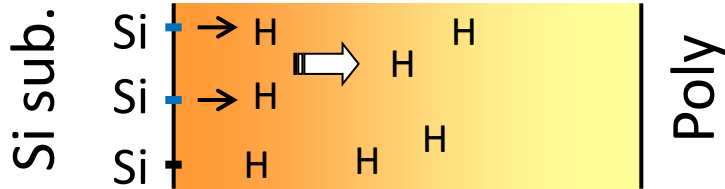
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# Basics of NBTI Model



# The Reaction-Diffusion Model



$$\frac{dN_{IT}}{dt} = k_F(N_0 - N_{IT}) - k_R N_H(0) N_{IT}$$

If  $dN_{IT}/dt$  is small, &  $N_{IT} < N_0$ ,

$$\left( \frac{k_F N_0}{k_R} \right) \approx N_H(0) N_{IT}$$

$$\frac{dN_{IT}}{dt} = D_H \frac{d^2 N_H}{dx^2}$$

$$N_{IT}(t) = \int_{x=0}^{x(t)=f(D_H, \mu_H, t)} N_H(x, t) dx$$

# Interface traps with diffusion of atomic H

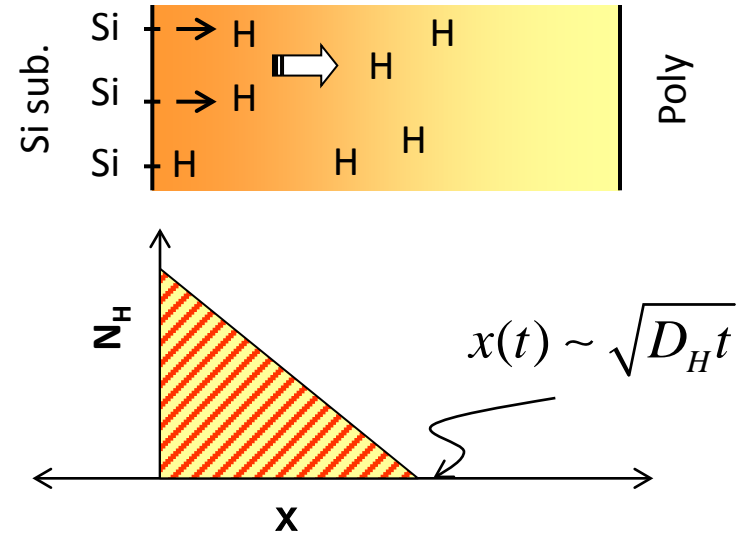
$$\left( \frac{k_F N_0}{k_R} \right) \approx N_H(0) N_{IT}$$

$$\begin{aligned} N_{IT}(t) &= \int_0^{\sqrt{D_H t}} N_H(x, t) dx \\ &= \frac{1}{2} N_H(0) \sqrt{D_H t} \end{aligned}$$

Combining these two, we get

$$N_{IT}(t) = \sqrt{\frac{k_F N_0}{2k_R}} (D_H t)^{\frac{1}{4}}$$

Jeppson, JAP, 1977.



simple differential equation gives rise to power-law !



# Interface traps with H<sub>2</sub> diffusion

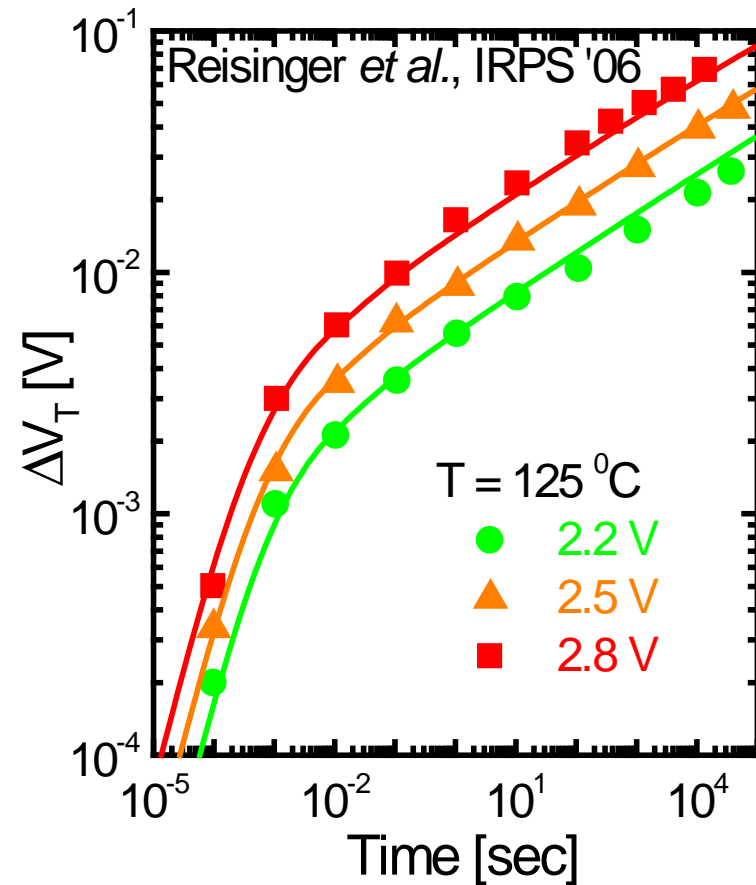
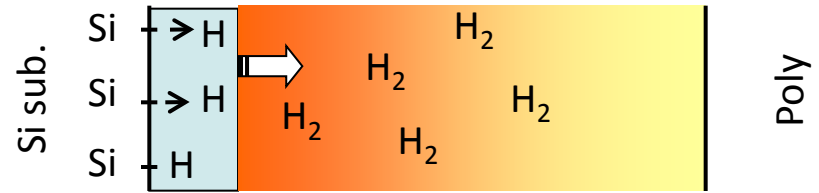
$$\left( \frac{k_F N_0}{k_R} \right) \approx N_H(0) N_{IT}$$

$$N_{IT}(t) = \frac{1}{2} N_{H_2}(0) \sqrt{D_{H_2} t}$$

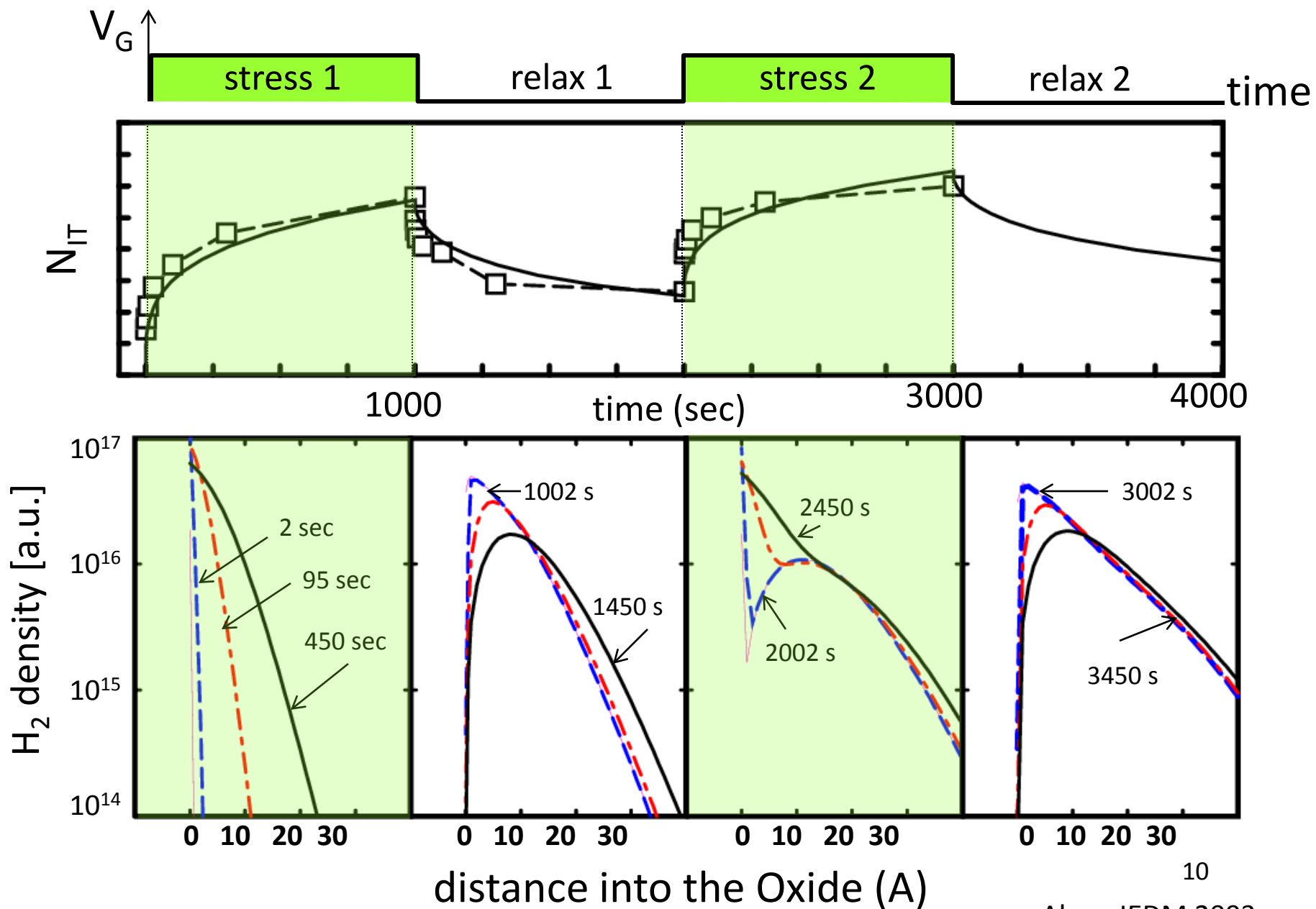
$$const. = \frac{N_H(0)^2}{N_{H_2}(0)} \quad (2H \rightleftharpoons H_2)$$

Combining the three, we get

$$N_{IT}(t) \propto \sqrt{\frac{k_F N_0}{2k_R}} (D_{H_2} t)^{\frac{1}{6}}$$



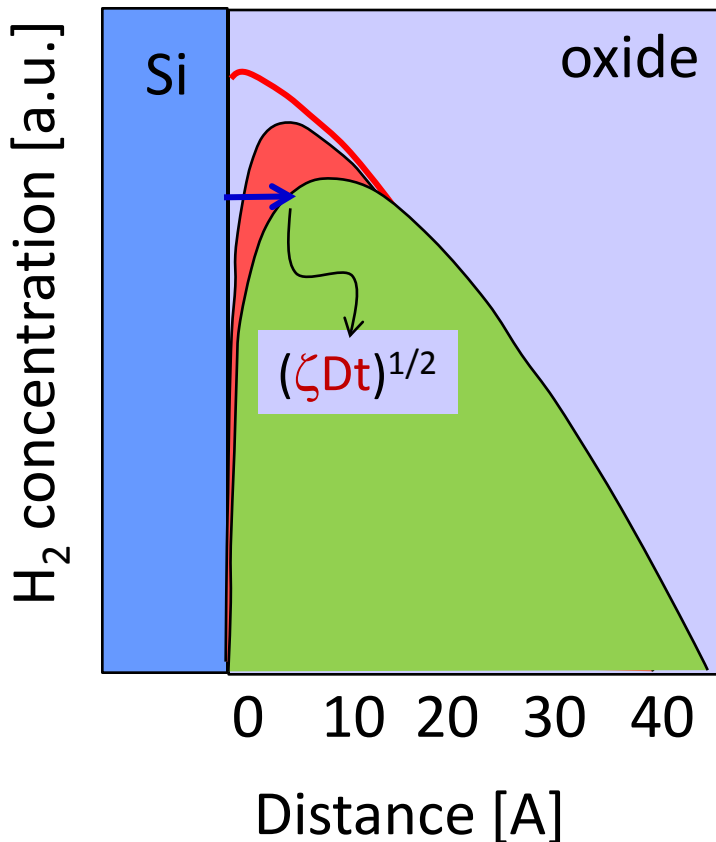
# Self-healing at AC stress



# NBTI relaxation

$$N_{IT}^{(0)} = \frac{1}{2} N_H(0) \sqrt{D_H \tau_0}$$

$$N_{IT}^{(*)} \approx \frac{1}{2} N_H(0) \sqrt{\xi D_H t}$$



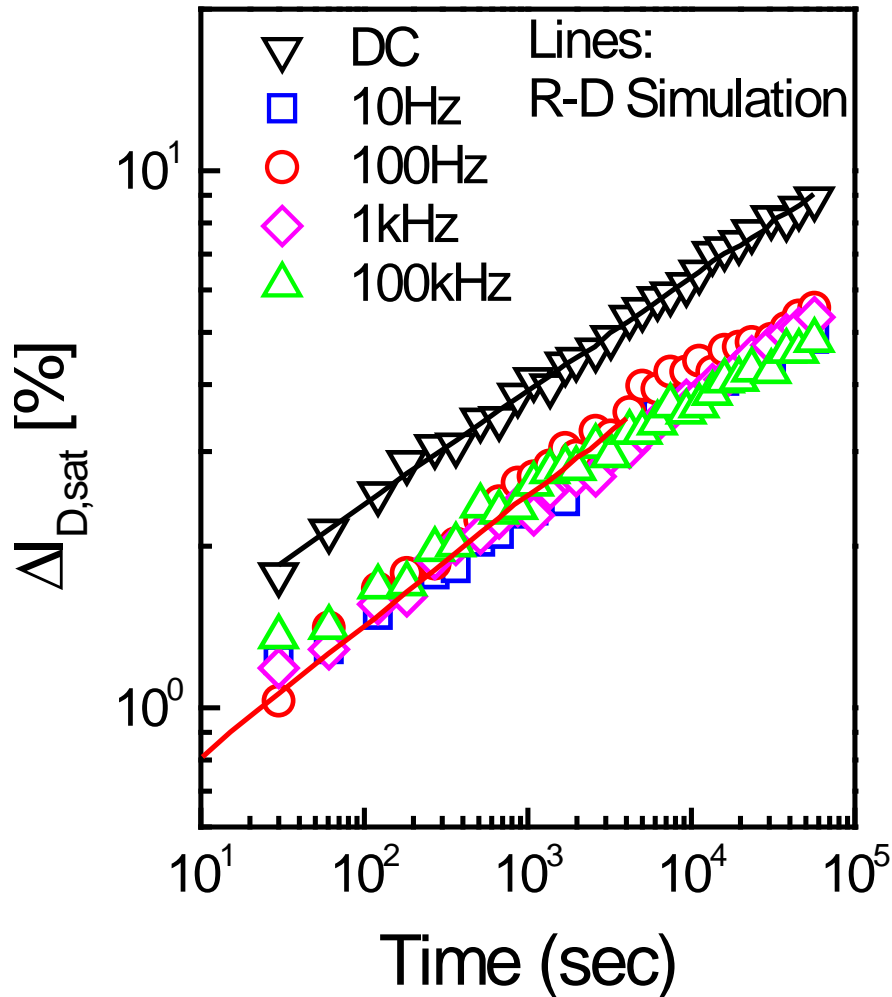
$$\frac{dN_{IT}}{dt} = k_F (N_0 - N_{IT}) - k_R N_H(0) N_{IT}$$

$$N_{H0} = N_{H0}^{(0)} - N_H^{(*)}$$

$$N_{IT} = N_{IT}^{(0)} - N_{IT}^{(*)}$$

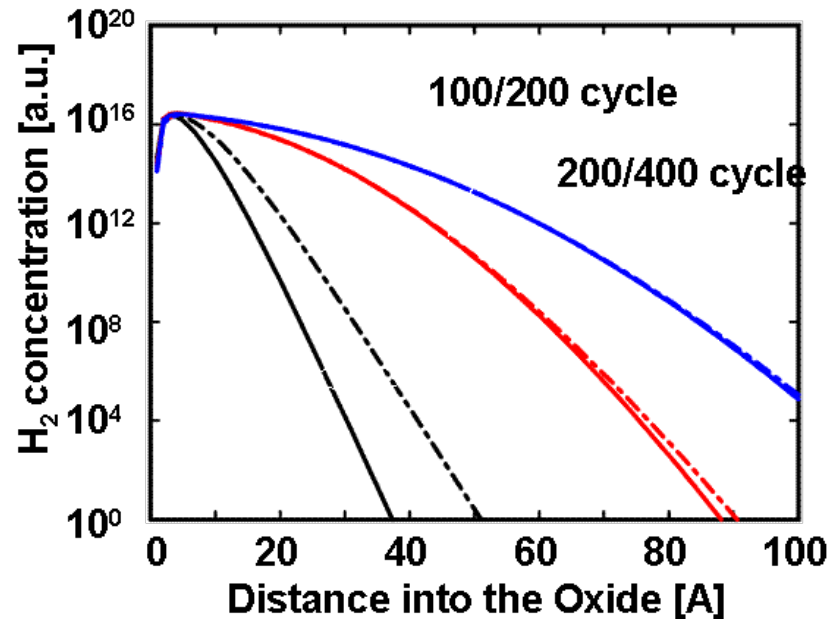
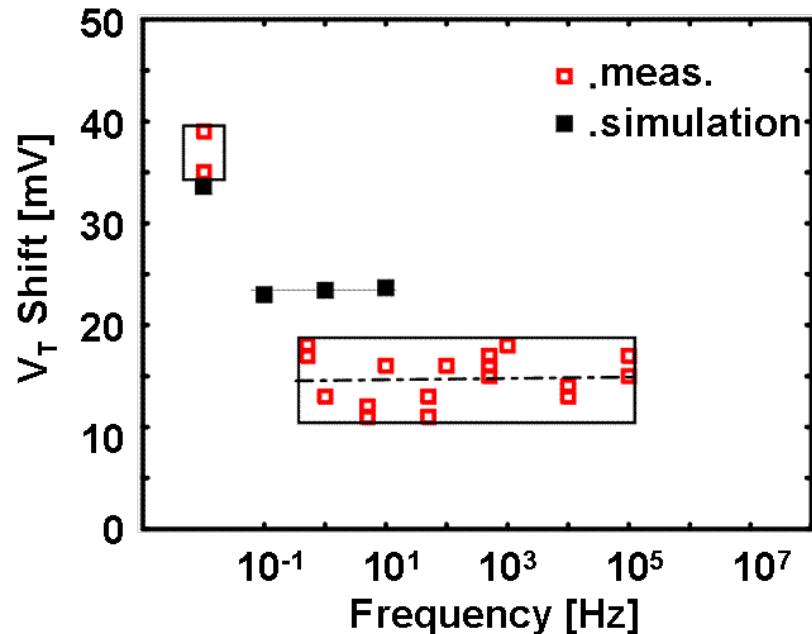
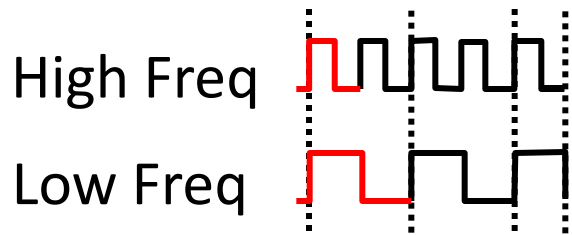
$$N_{IT} = N_{IT}^{(0)} \left( 1 - \sqrt{\frac{\xi t / \tau_0}{1 + t / \tau_0}} \right)$$

# Frequency independent degradation



- Both AC and DC NBTI degradation show same time characteristics.
- Experiments show that frequency independence holds till at least 2 GHz

# NBTI model for frequency independence



Smaller duty cycle reduces  $V_T$  shift ...

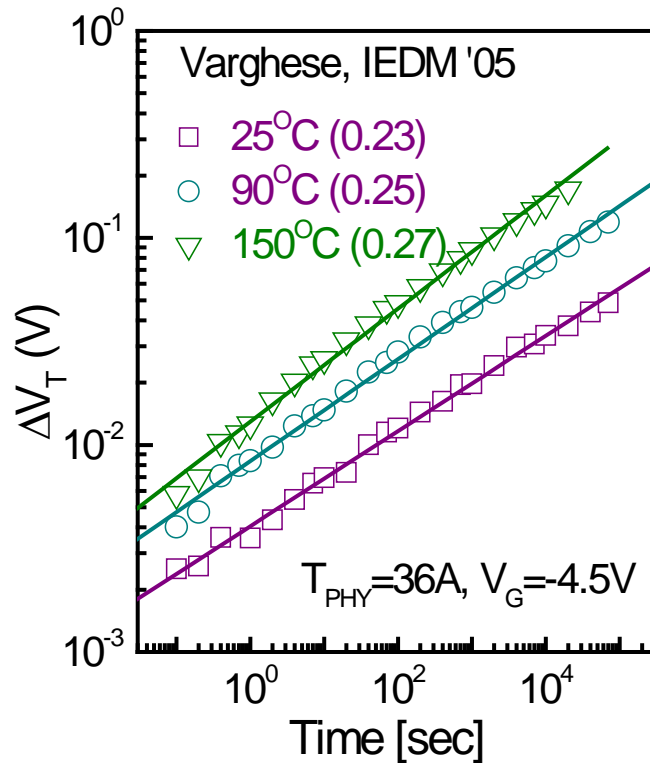
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# An enduring puzzle

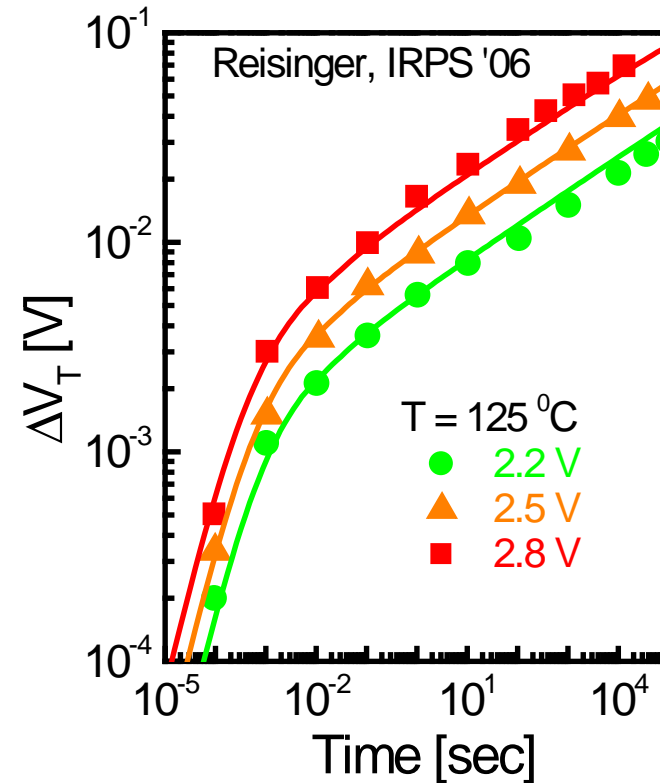
## Classical measurement

$$\Delta V_T = A_1 t^{1/4}$$



## Modern On-the-fly meas.

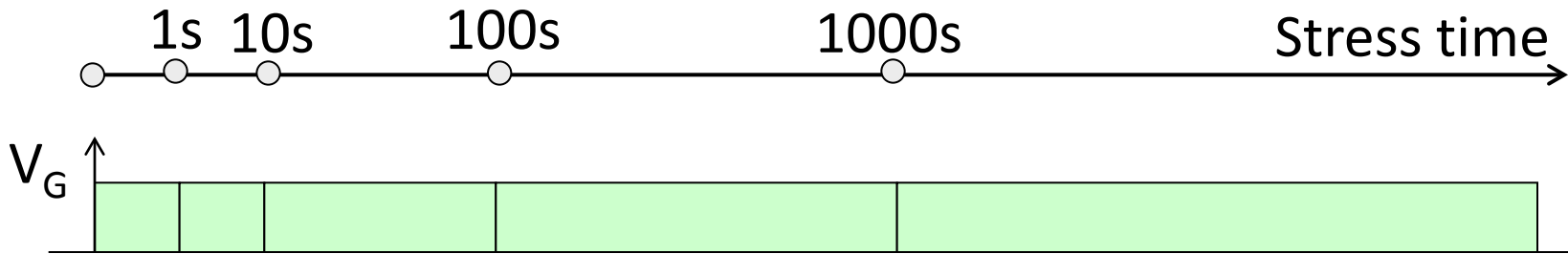
$$\Delta V_T = A_2 t^{1/6}$$



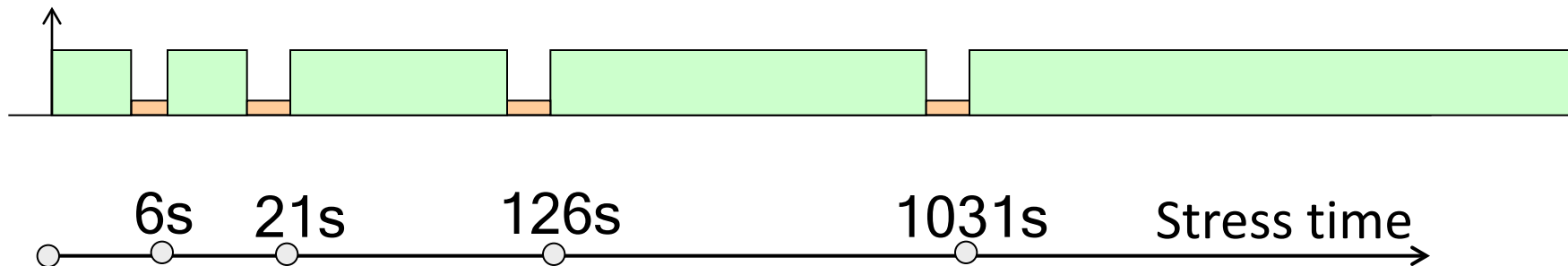
Two different ways of measurement give two different results !

# Measurement changes the NBTI degradation

What we **think** we do during measurement ...



What we **actually** do during measurement ...



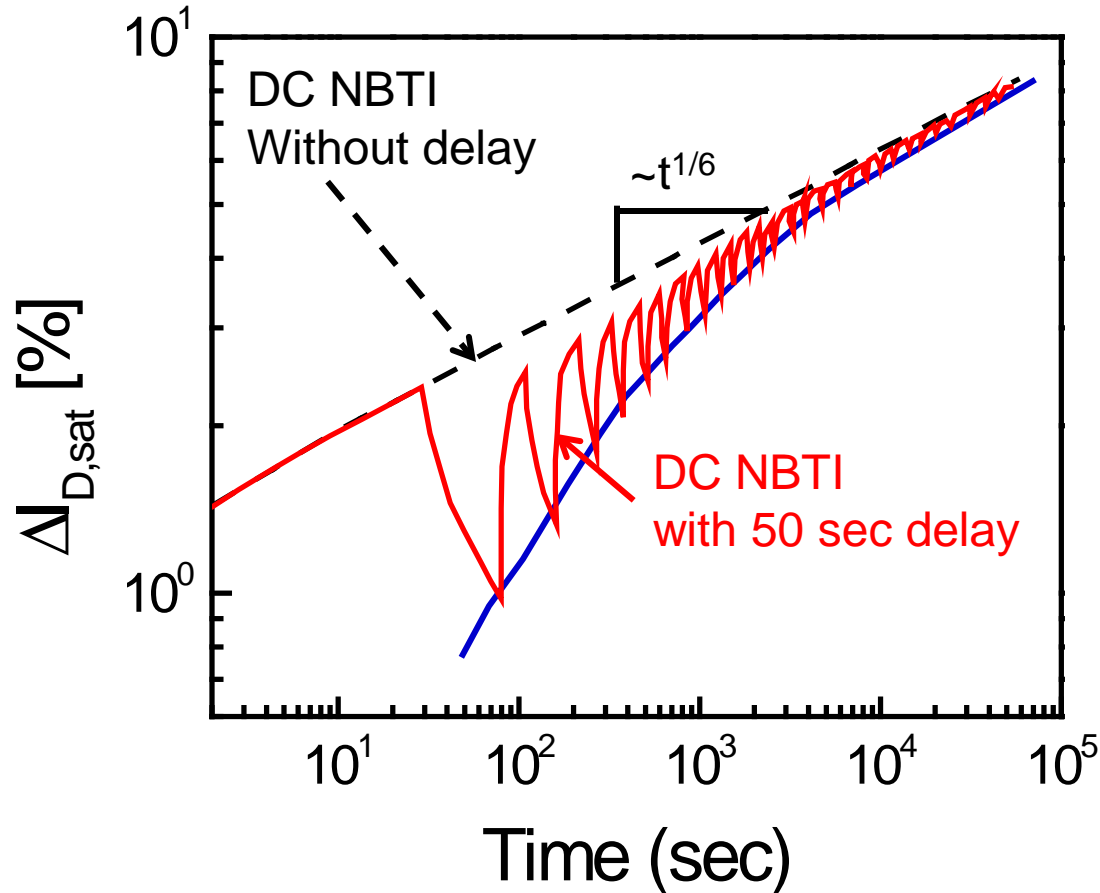
\* 5 sec. measurement window (for example).

S. Rangan, Intel, IEDM 2003.

Measurement is like a variable frequency AC stress ....



# More measurement & less (!) accuracy

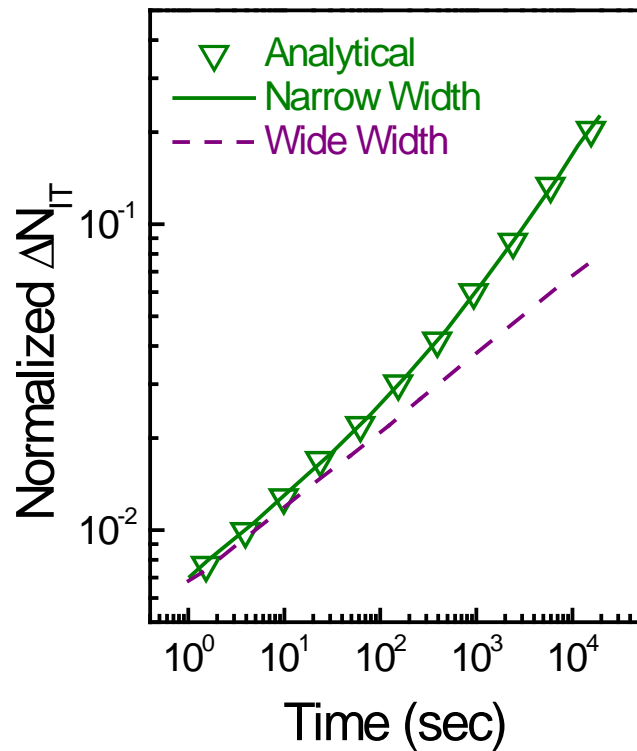
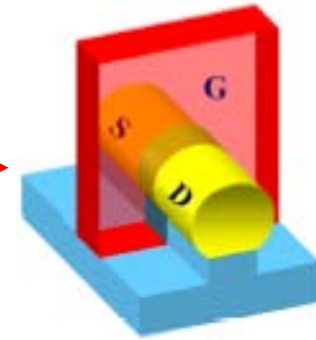
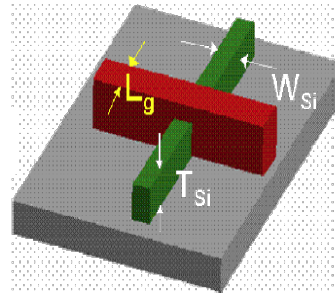
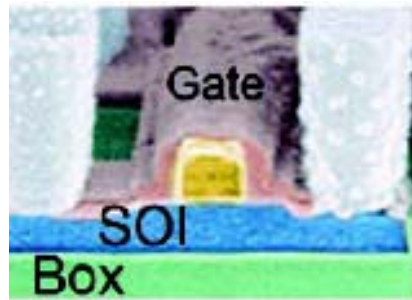


Actually,  $n=0.16$  at all times (H<sub>2</sub> diffusion), measurement delay makes it appear  $n=0.25$  at short times. A 40 year old puzzle finally resolved!

# Outline of lecture 10

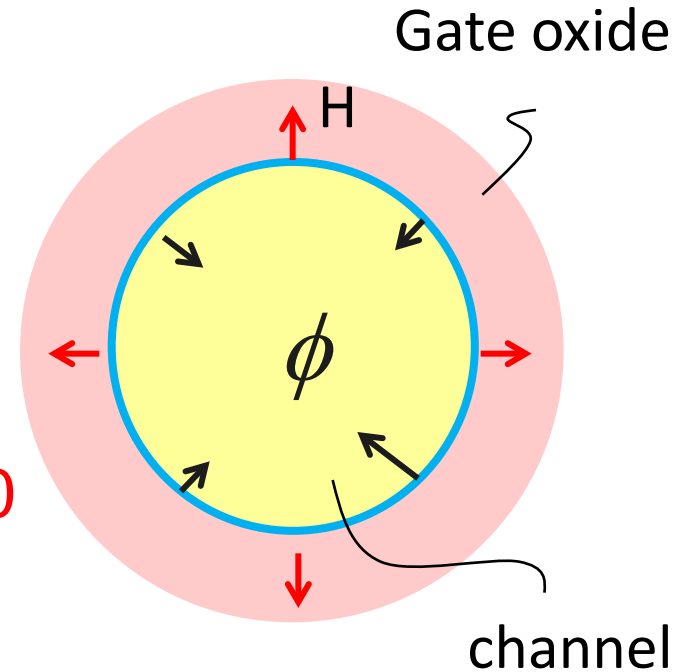
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# Non planar devices



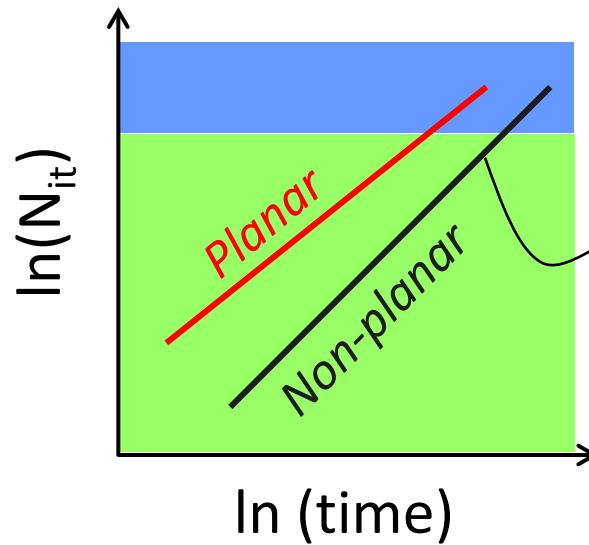
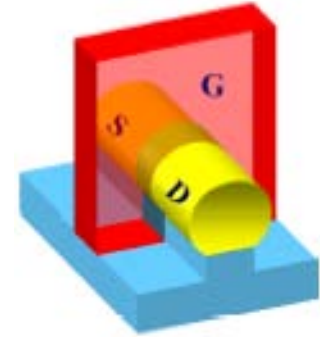
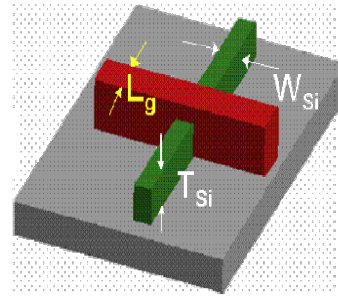
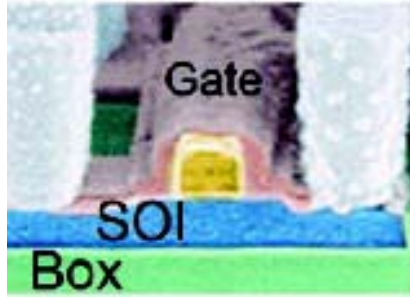
$$\epsilon \nabla^2 \phi = 0$$

$$D_H \nabla^2 N_H = 0$$



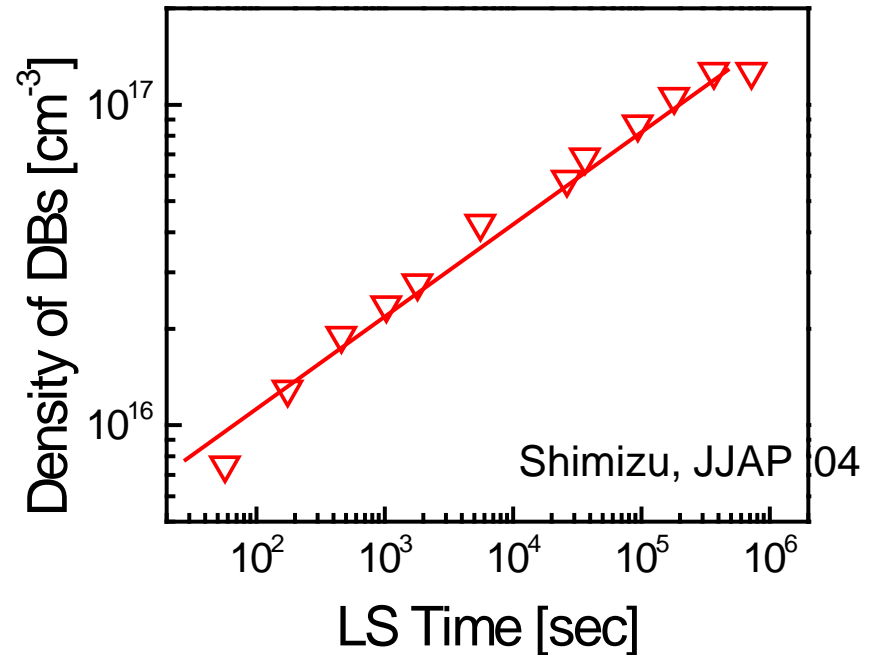
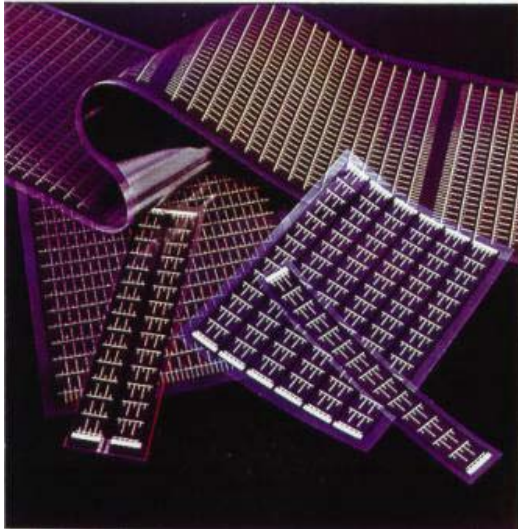
Reliability theory anticipates performance-degradation trade-off.

# Performance and reliability



Higher slope, but lower degradation at lower operating voltage

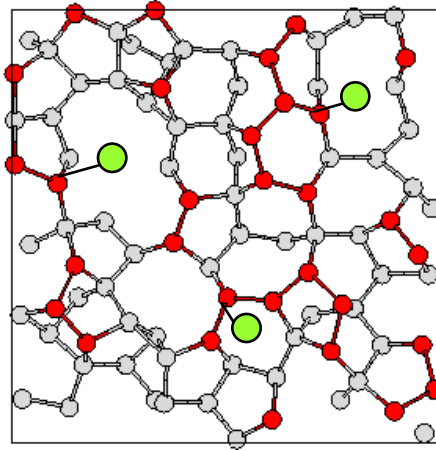
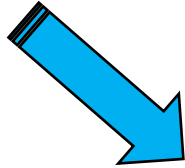
# Light-induced degradation in solar cells



Light induced degradation has a time exponent of  $n=1/3$

# Reaction-diffusion model for LID

G



3-fold coordinated  
Surface atoms of a-Si.

Green – H

Red – surface Si

White -- Bulk

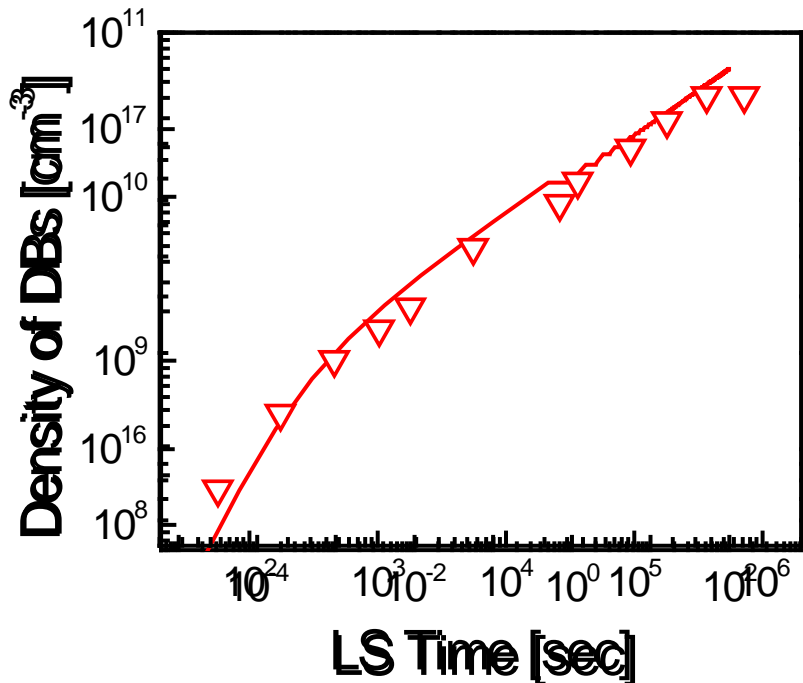
Reaction:

$$\frac{dN_{DB}}{dt} = k_F N_0 G - k_R N_{DB} N_H \sim 0$$

Free H Generation:

$$\frac{dN_H}{dt} = \frac{dN_{DB}}{dt} - k_H N_H^2$$

$$N_{DB} \propto (3k_H)^{1/3} \left( \frac{k_f N_0 G}{k_r} \right)^{2/3} t^{1/3}$$



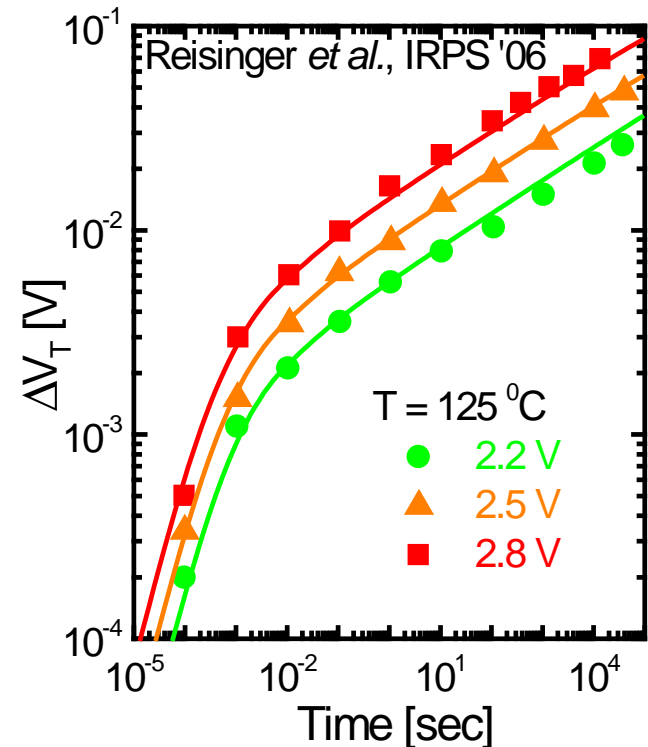
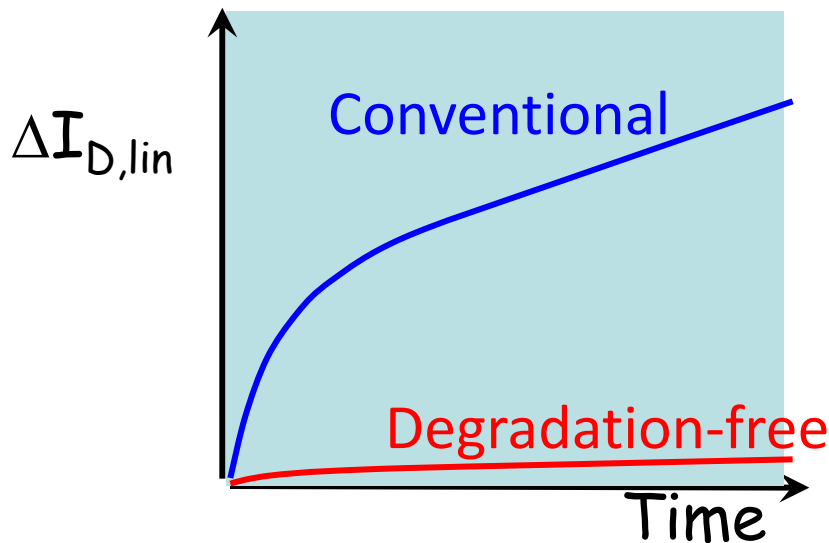
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# NBTI-aware logic and degradation-free transistors (A. E. Islam)

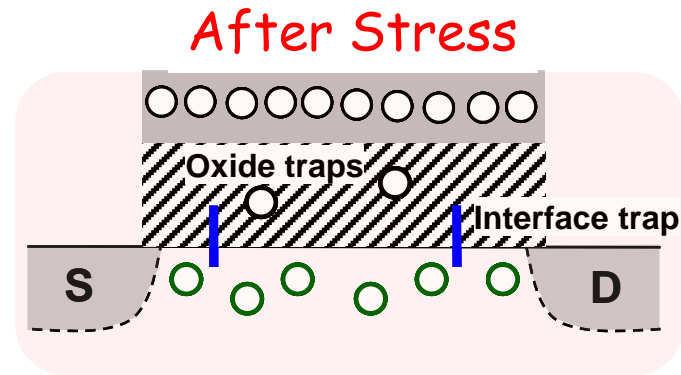
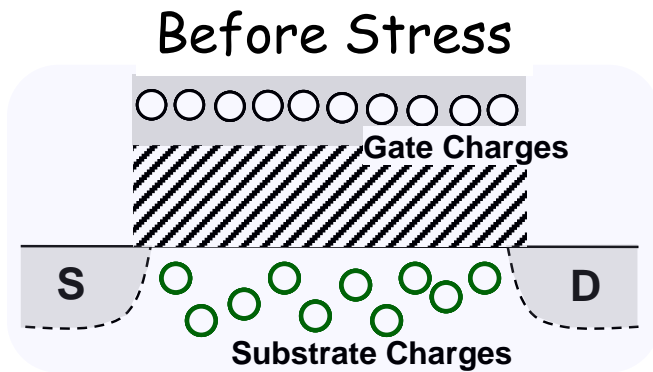
$$\left( \frac{\Delta I_D}{I_{D0}} \right) = \frac{\Delta \mu_{\text{eff}}}{\mu_{\text{eff0}}} - \left( \frac{\Delta V_T}{V_G - V_{T0}} \right) \quad I_D = A \mu_{\text{eff}} (V_G - V_T)$$

If we could make  $\Delta \mu$  positive ...

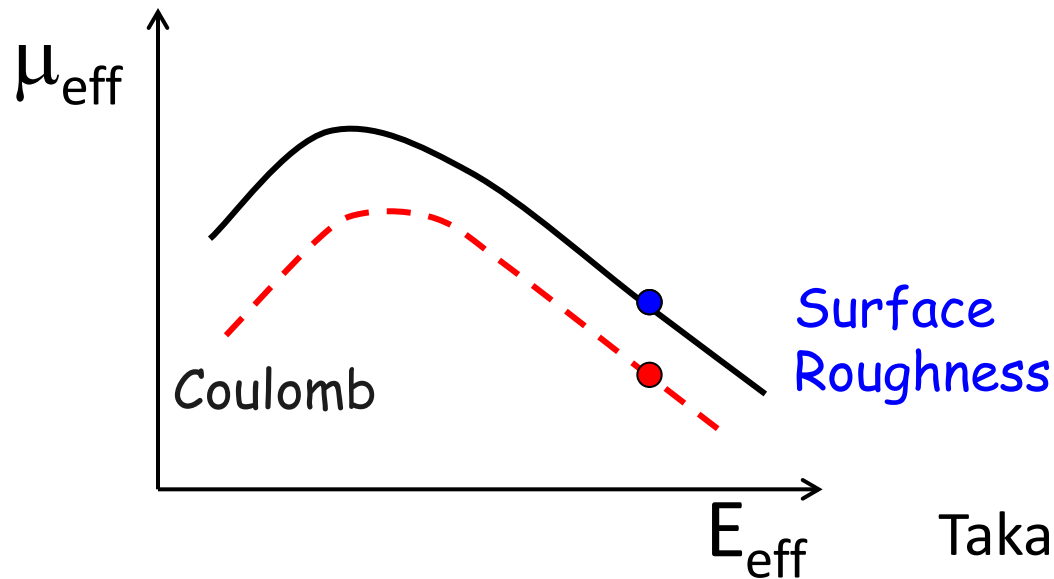




# Mobility and VT-shift

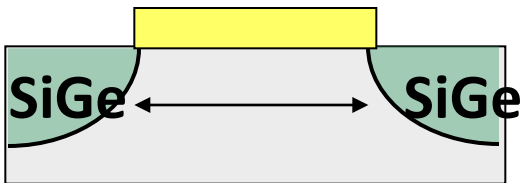
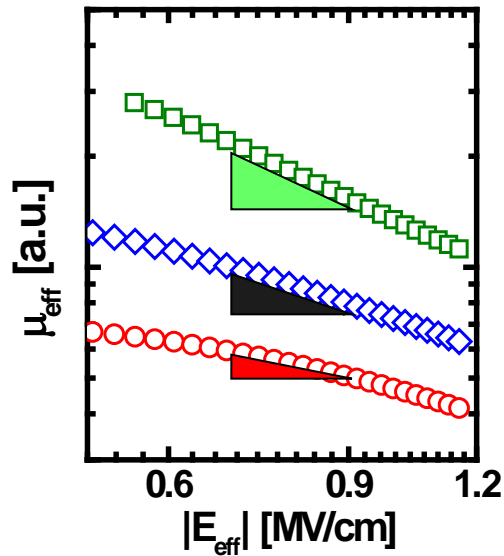


$$E_{\text{eff}} = Q_{\text{dep}} + \eta Q_{\text{inv}} \sim (V_G - V_T)$$

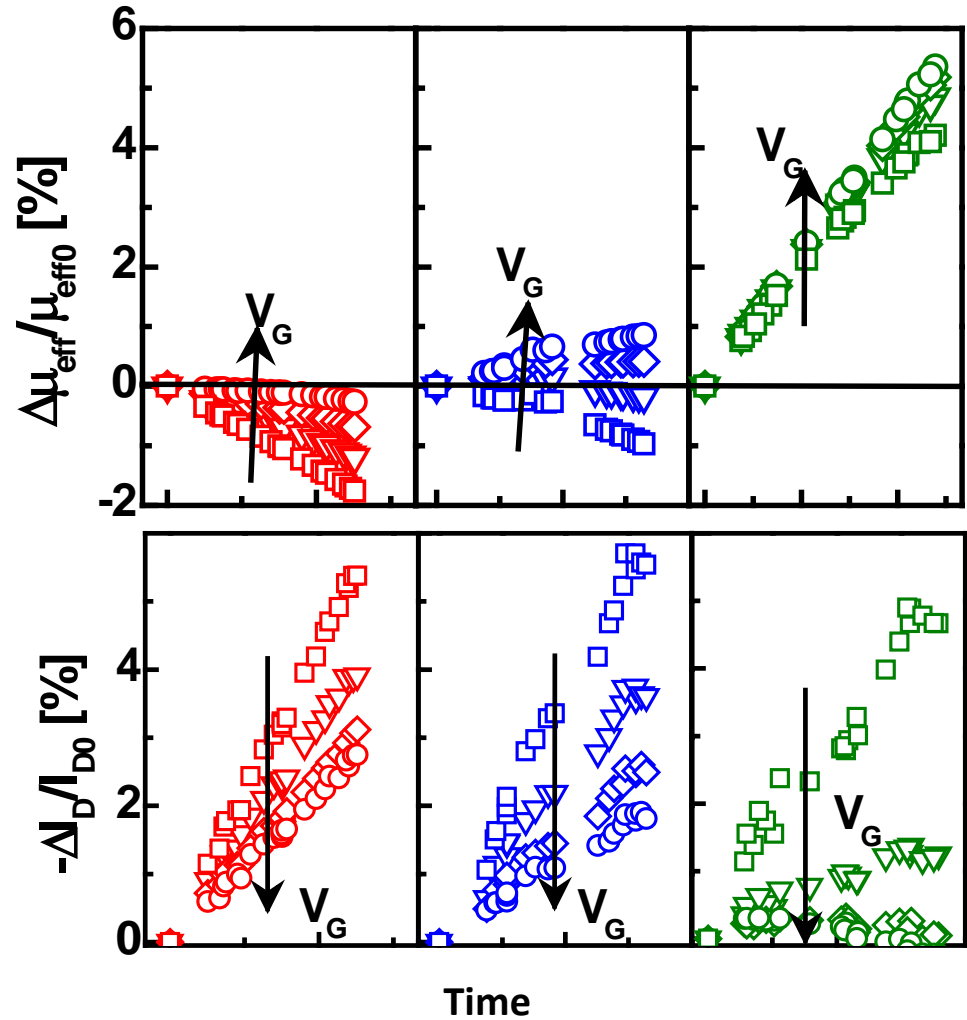


# Degradation-free logic transistors ...

$$\frac{\Delta I_D}{I_{D0}} = \frac{\Delta \mu_{\text{eff}}}{\mu_{\text{eff}0}} - \frac{\Delta V_T}{V_G - V_{T0}}$$

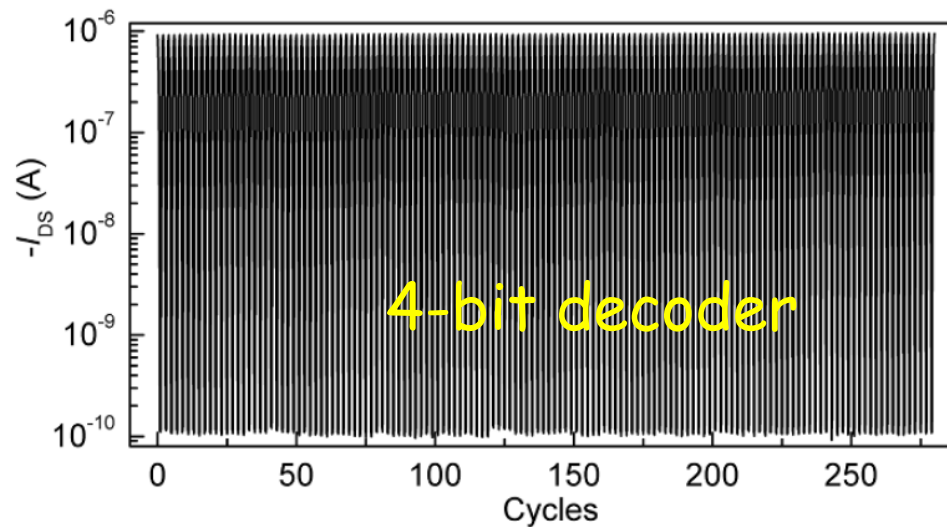
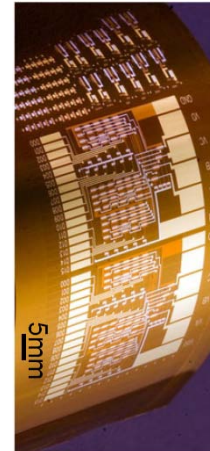
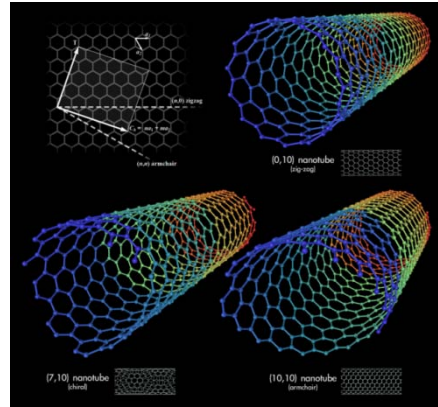


By strain engineering!



Steep  $\mu_{\text{eff}}$  vs.  $E_{\text{eff}} \rightarrow$  Negligible  $\Delta I_D$

# Implications for CNT-based TFT reliability

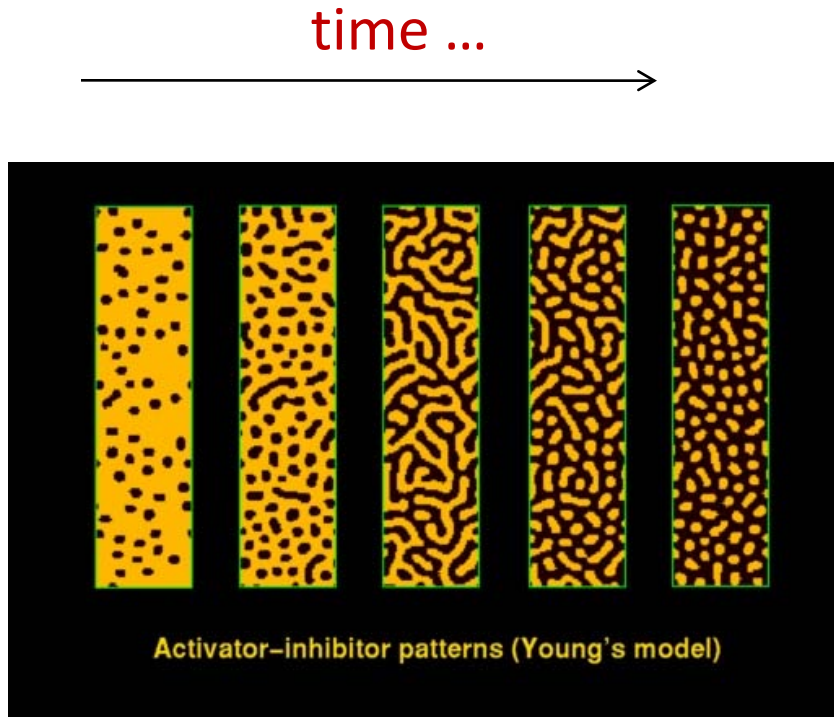


Hydrogen-free interfaces may have no interface traps ...

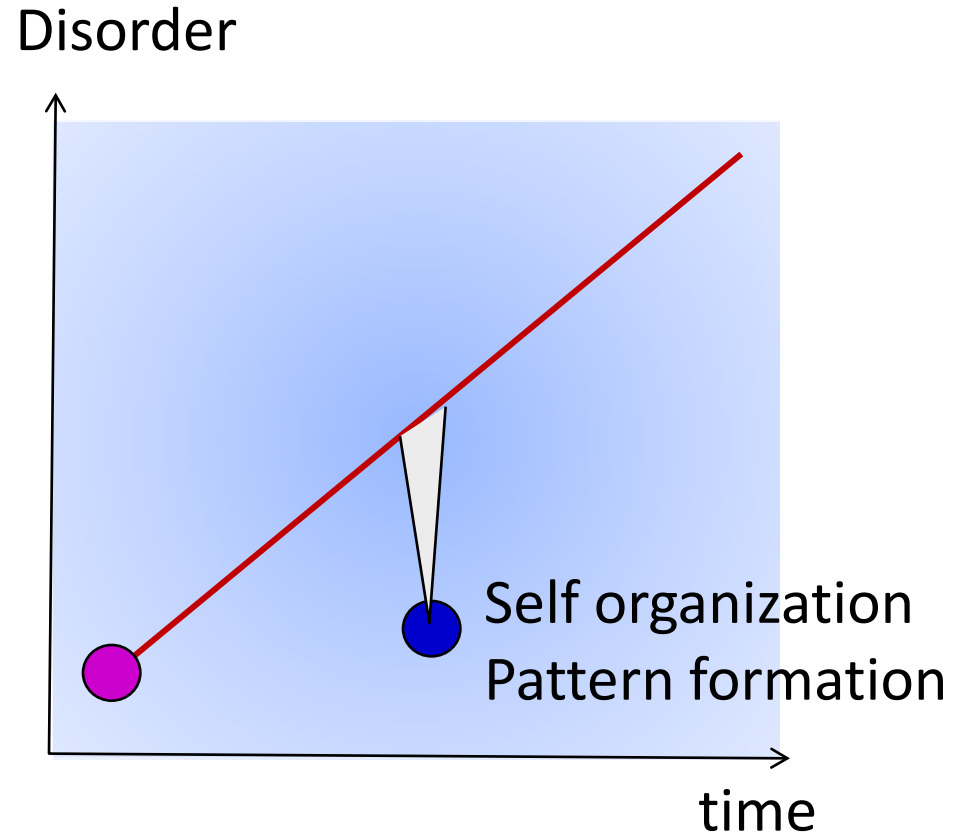
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# The power of reaction-diffusion model



Turing's model of Morphogenesis, 1953.

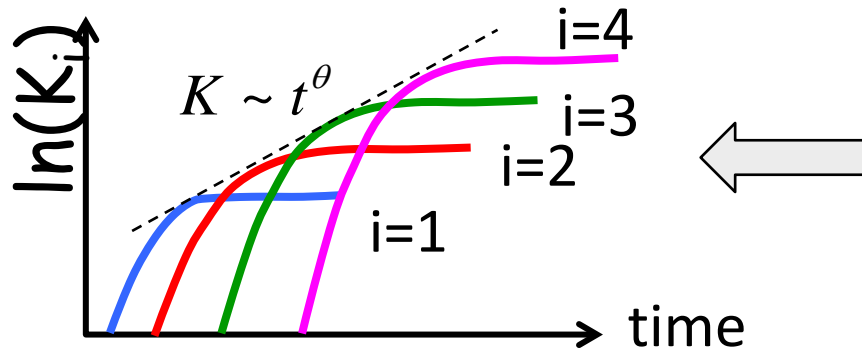


Prigogine, "From being to becoming", 1980.

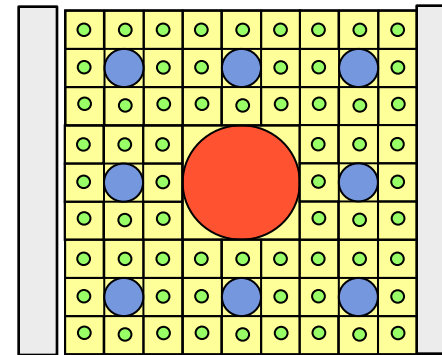
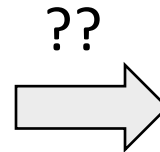
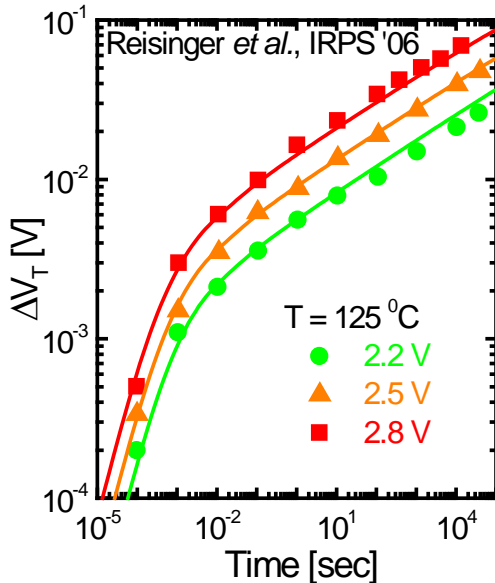
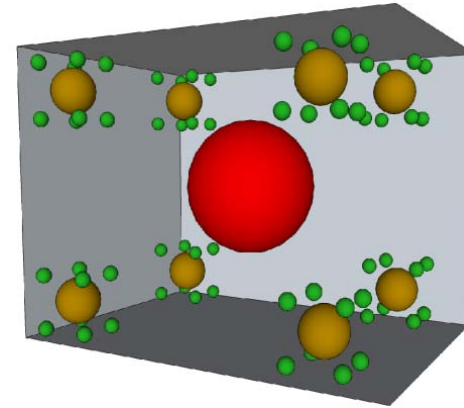
Reaction-diffusion model produces complex structures out of homogenous systems

# Power laws, fractals, SPICE models

Power-laws



Fractals



$$I_T = f(V_D, V_G) \times \xi \left( \frac{L_C}{L_S}, D_C L_S^2 \right)$$

A classical device may become fractal over a period of time ...

# Conclusions

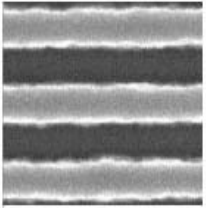
- NBTI has been one of the most important reliability challenge since the very inception of CMOS.
- The very strange properties of NBTI involving power-law time exponent, relaxation, frequency independence arise from the peculiar properties of reaction-diffusion models.
- Initially presumed different, NBTI in PMOS transistors and LID in a-Si solar cells appear to arise from the same physical phenomena.
- It is possible to design a degradation free transistors. Degradation-free does not mean defect-free devices.
- Finally, reaction-diffusion model appears to self-organize ordered surfaces. If this is also true for NBTI, the entire literature of NBTI spice model will have to be revisited.

epilogue

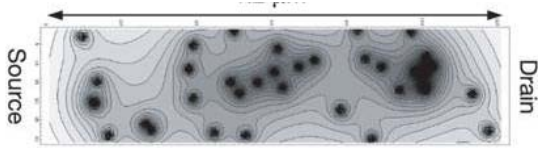


# Disorder and Ohm's law

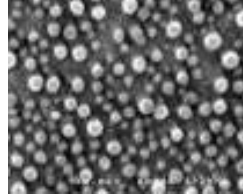
Line Edge Roughness



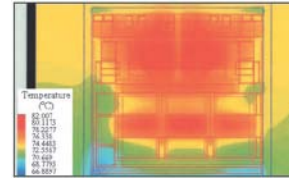
Random Dopants



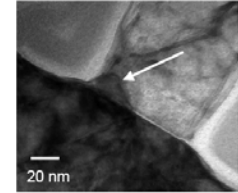
NC Flash



Non-homo. T

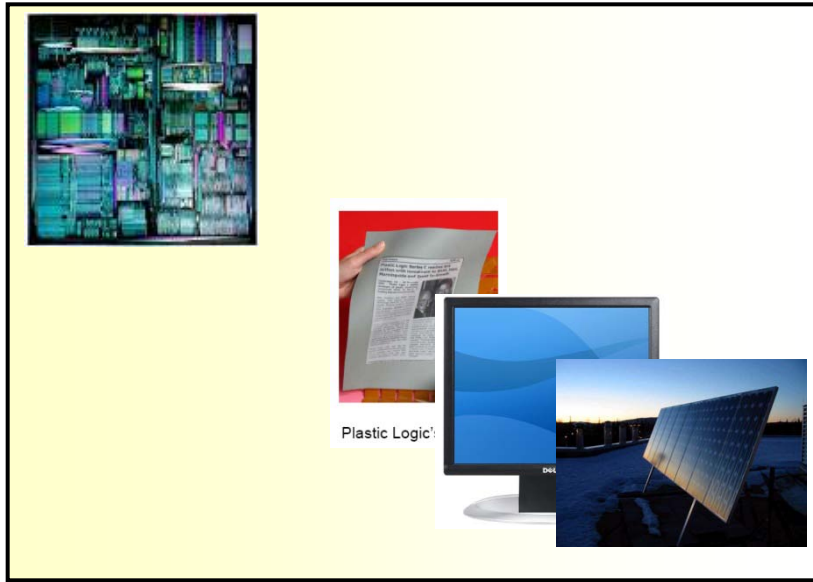


Dielectric BD



Performance

high  
medium  
low



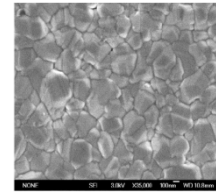
small

medium

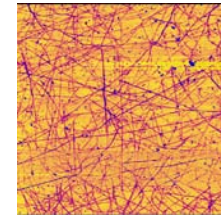
large

Area

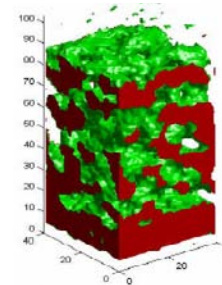
Poly-Si



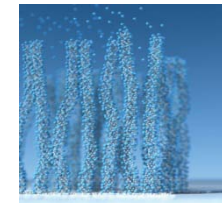
NanoNet/ Biosensors



Solar cells



super-capacitors



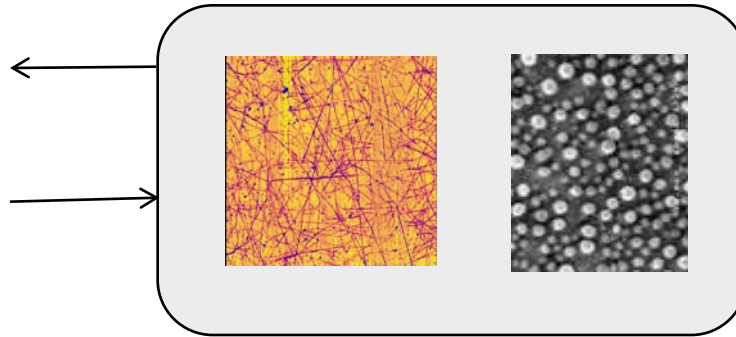
$$G \propto \frac{\tau}{m^*} \frac{1}{L}$$

Does not mean what it used to ...

# Theory and Application

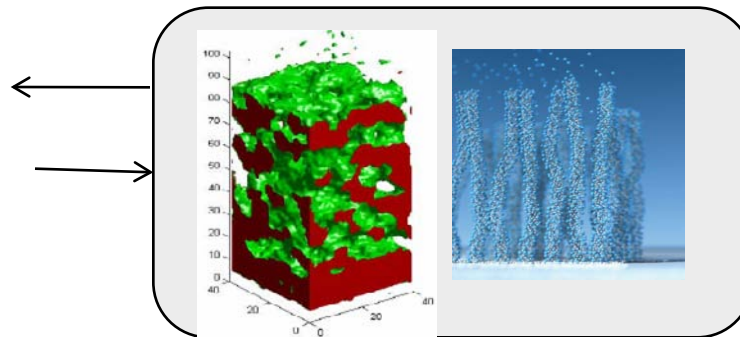
Nonlinear

Percolation



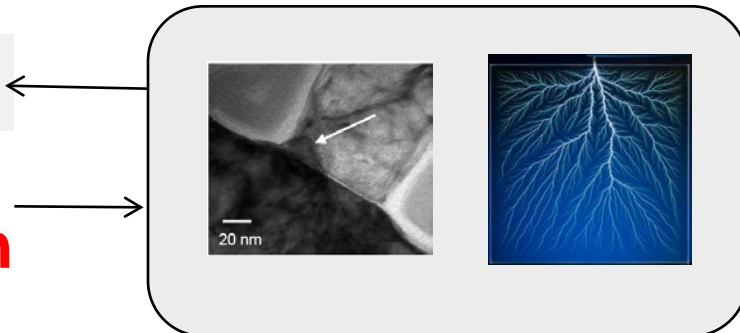
Finite

Fractals



Correlated

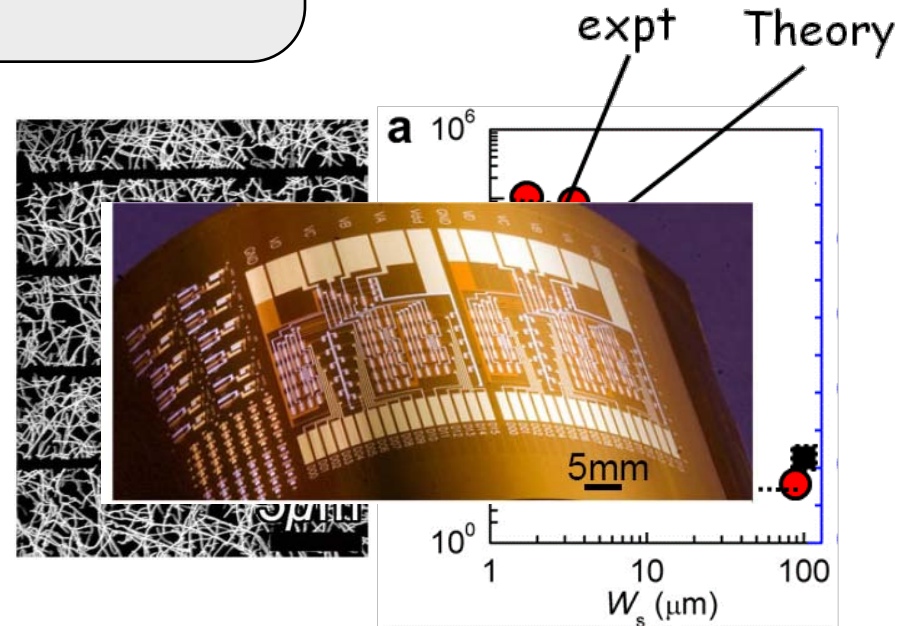
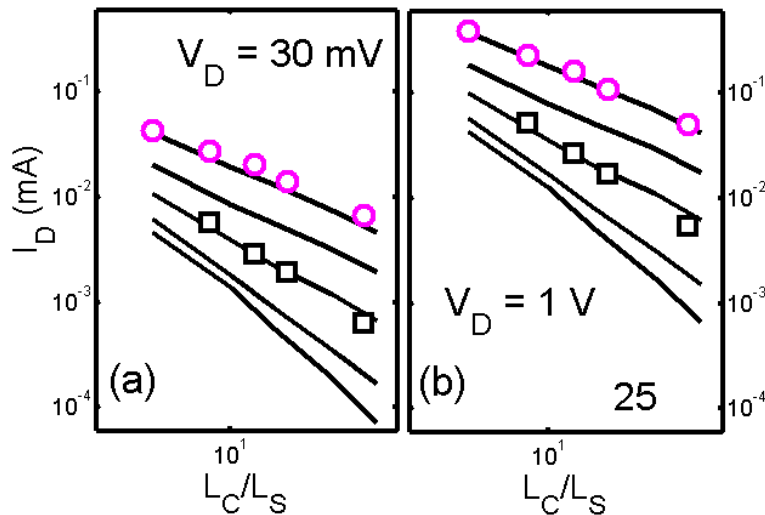
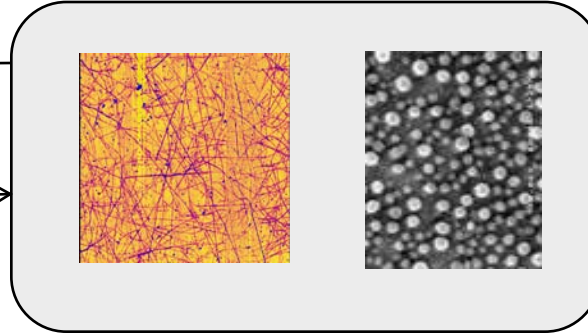
Temporal  
Percolation



# Nonlinear Stick Percolation for Electronic Devices

Nonlinear

Percolation

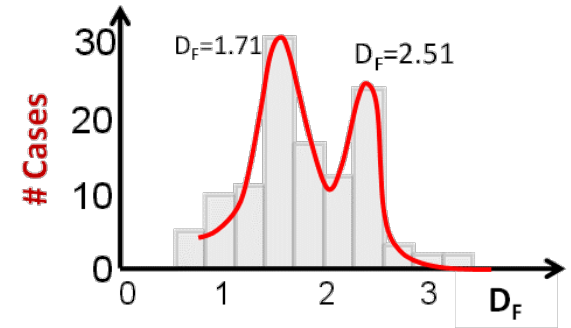
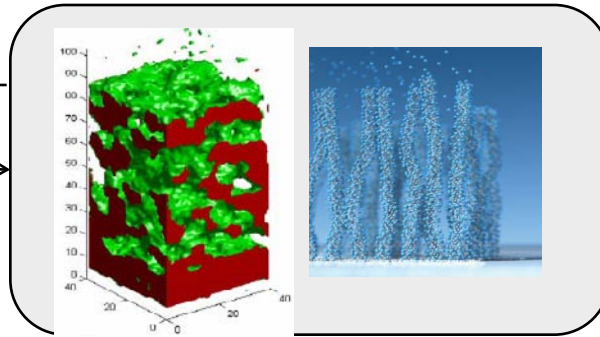


$$I_D = f(V_D, V_G) \times \xi \left( \frac{L_C}{L_S}, D_C L_S^2 \right)$$

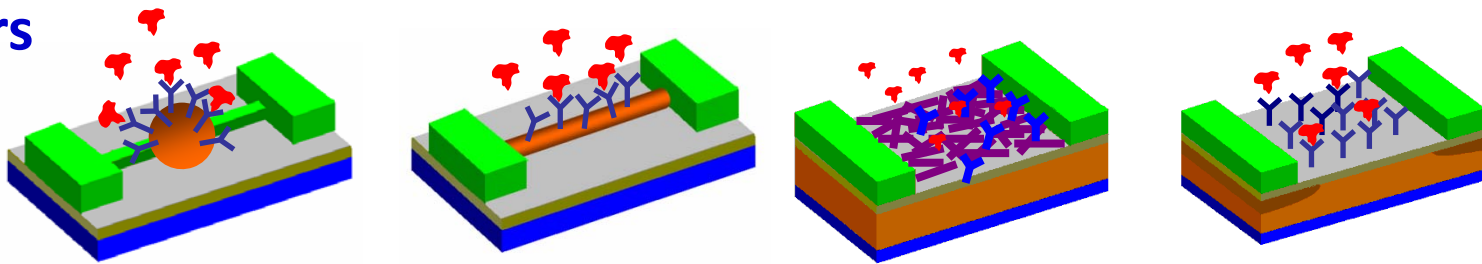
Width dependent  
On/Off ratio ...

# Response of Fractal Surfaces

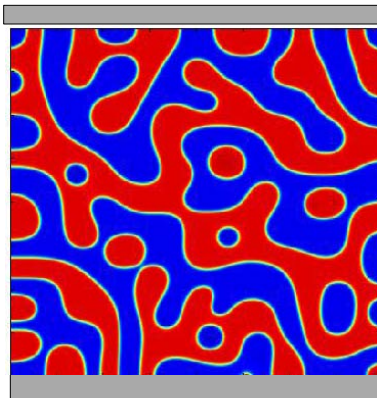
Finite  
Fractals



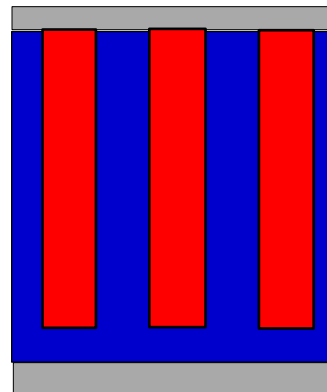
Sensors



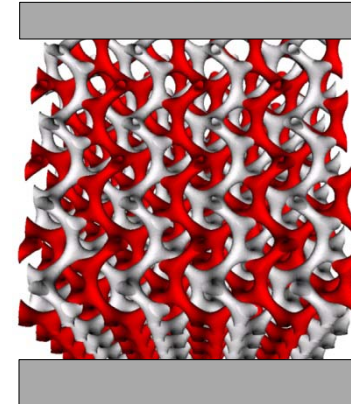
Spinodal



Ordered



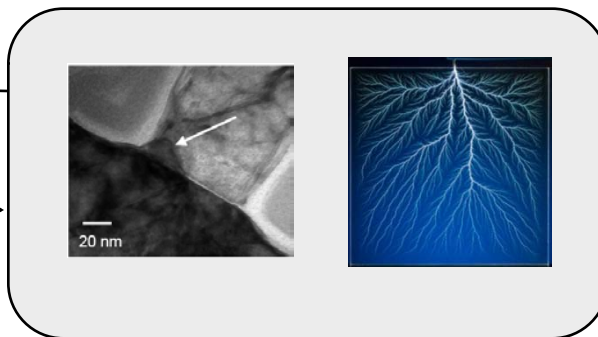
Double Gyroid



Solar Cells

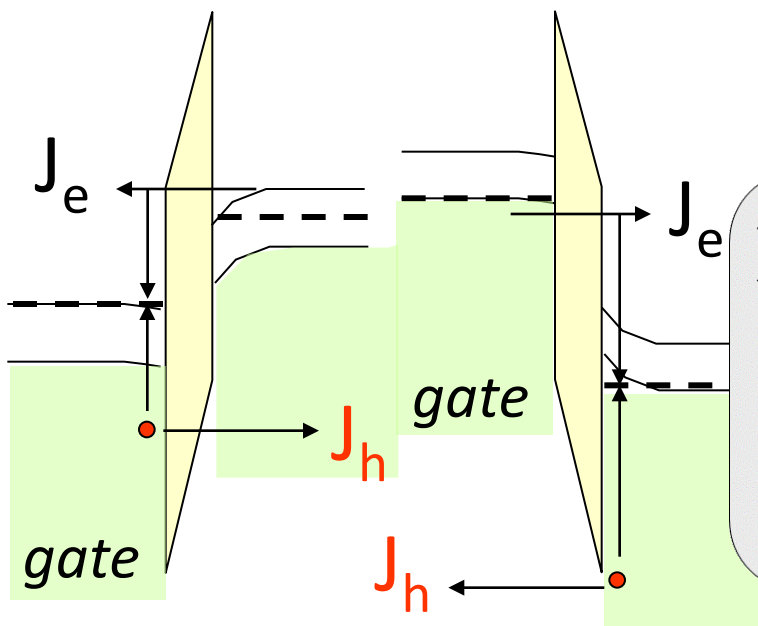
# Reliability and Dielectric Breakdown

Correlated  
Temporal  
Percolation

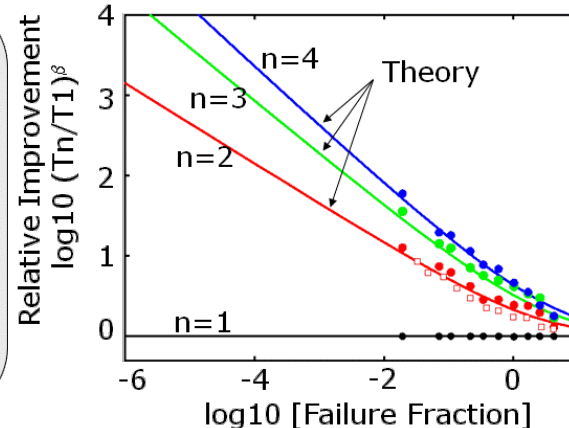
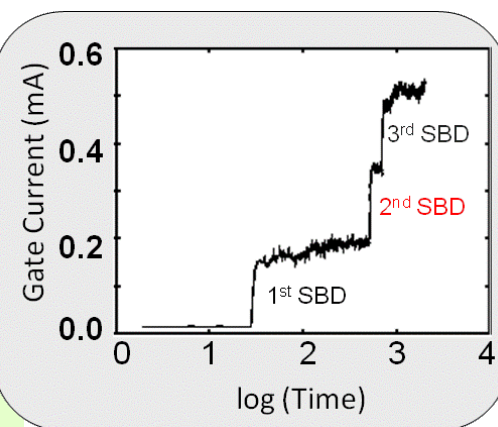


NMOS

PMOS

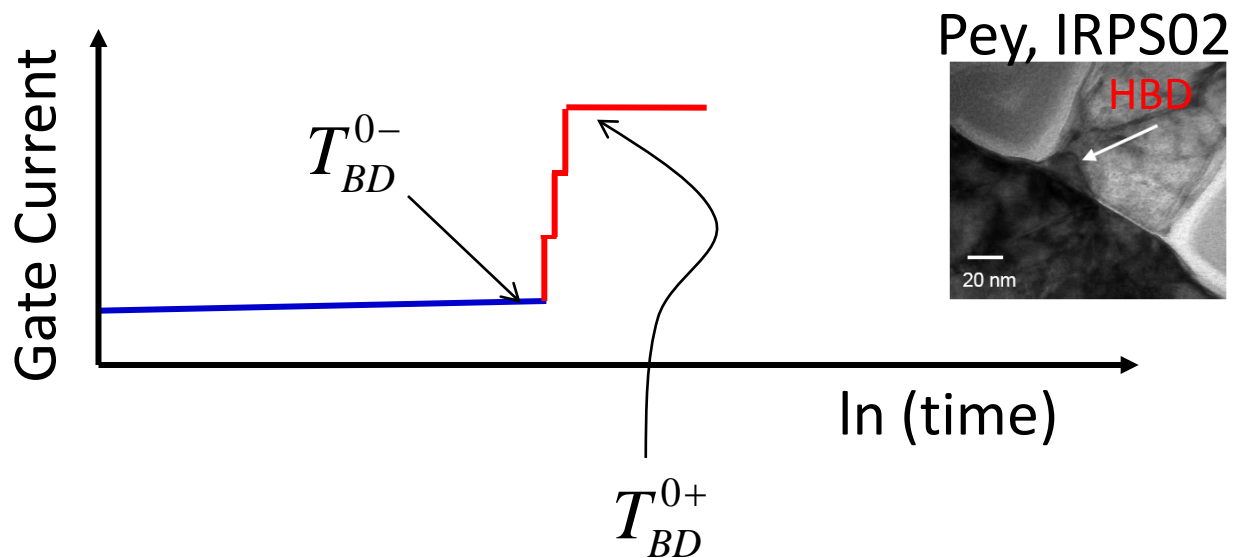
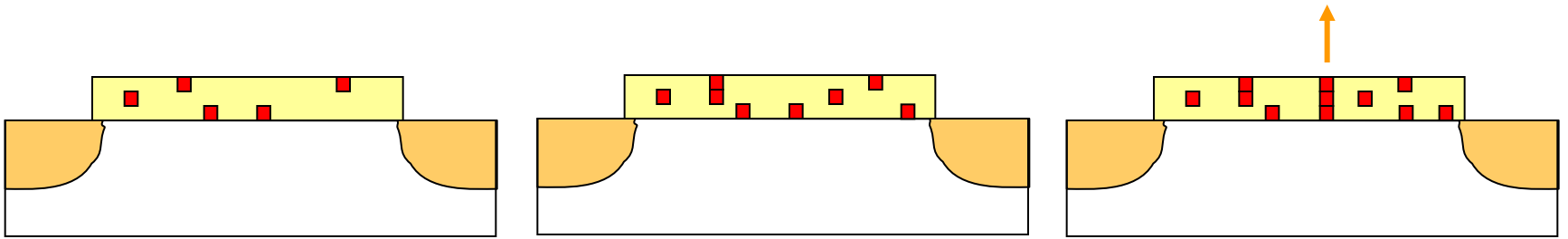


$$\left( \frac{T_n}{T_1} \right)^\beta = \frac{n (2\pi n)^{1/2n}}{e F_n^{(1-1/n)}}$$

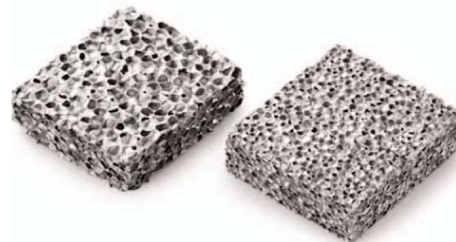
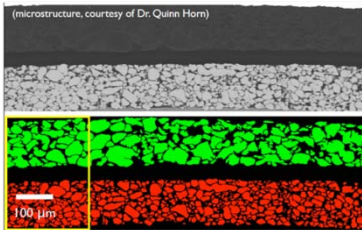
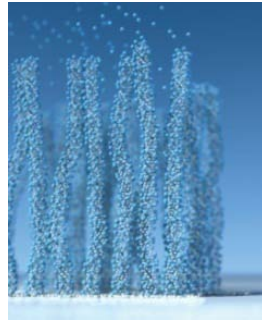
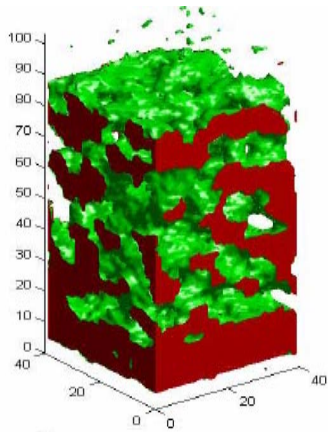


# Why is reliability predictable?

distinction between  $T_{BD}(0^+)$  vs.  $T_{BD}(0^-)$



# On random materials and biomimetic design



Life at the edge of equilibrium thermodynamics uses geometry in remarkable ways ... description of that geometry is essential in understanding the function of biomimetic materials and devices